

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. 09/652,534
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Inventor Sujit Sharan et al.
Assignee Micron Technology, Inc.
Priority Group Art Unit 2823
Priority Examiner Trung Q. Dang
Attorney's Docket No. MI22-2360
Title: Plasma Enhanced Chemical Vapor Deposition Methods and Semiconductor
Processing Methods of Forming Layers and Shallow Trench Isolation
Regions

PRELIMINARY AMENDMENT

To: Mail Stop Patent Application
Commissioner for Patents
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VIA HAND DELIVERY

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Sir:

This is a preliminary amendment accompanying a Request for Continuation Application for the above-entitled patent application. Prior to examining the application, please enter the following amendments.

AMENDMENTS

Underlines indicate insertions and ~~strikeouts~~ indicate deletions.